Akira Sekiguchi[†] and Wataru Ando*

Department of Chemistry, The University of Tsukuba, Niihari-gun, Ibaraki 305, Japan

Received January 26, 1987

Photolyses and pyrolyses of (pentamethyldisilanyl)diazomethane (1), (pentamethyldisilanyl)(trimethylsilyl)diazomethane (2), and (tris(trimethylsilyl)silyl)(trimethylsilyl)diazomethane (3) resulted in the formation of the corresponding π -bonded silenes by the exclusive migration of a trimethylsilyl group to a carbene center. The silenes were efficiently trapped by alcohols and carbonyls. The ultraviolet absorptions of the silenes have also been measured.

Introduction

Research on sp²-hybridized silenes is of current interest, and the chemistry achieved has been summarized in many reports.¹ Although there are many methods to generate silenes, one typical approach to silenes is the intramolecular reactions of α -silylcarbenes (eq 1).² In a previous

$$-\overset{I}{\text{Si}}\overset{I}{\longrightarrow}\overset{I}{\text{Si}}=\overset{I}{\text{C}}\overset{I}{\underset{R}{\longrightarrow}}$$

paper, we reported that the migrating ability of the groups on silicon atom to a carbene center was not influenced on the nature of substituents but was dependent on the statistical factor.³ Since the Si–Si bond has shown σ -electron-donating properties⁴ and the bond is relatively weaker than Si–C bonds,⁵ silylcarbenes having an Si–Si bond are expected to undergo selective migration of a trimethylsilyl group to a carbene center, giving silenes. We report here such silyl migrations in the photoinduced and thermal decompositions of polysilylated diazomethanes 1, 2, and 3.⁶



Results and Discussion

Photochemical and Thermal Decompositions of Polysilylated Diazomethanes 1, 2, and 3. Photolysis of (pentamethyldisilanyl)diazomethane (1) in *tert*-butyl alcohol with a high-pressure mercury lamp ($\lambda > 300$ nm) gave *tert*-butoxysilane 5 which arose from the trapping of silene 4 in 41% yield. Similarly, photolysis in the presence of acetone gave a silyl enol ether 6 in 28% yield (Scheme I).

Flash vacuum pyrolysis of 1 at 450 °C produced 1,3disilacyclobutane 7 in 47% yield (a mixture of cis and trans isomers; ratio 41:59), apparently formed by the head-to-tail dimerization of the silene 4. The silene was further intercepted by *tert*-butyl alcohol and carbonyl compounds. When 1 was pyrolyzed with *tert*-butyl alcohol at 450 °C in a stream of nitrogen, *tert*-butoxysilane 5 was obtained in 53% yield. Co-pyrolysis of 1 with acetone gave the silyl enol ether 6 in 54% yield and with benzophenone led to



the formation of vinylsilane 8 in 58% yield via the Wittig-type reaction of the silene 4 with the ketone (Scheme

Bioorganosilicon Chemistry; Sakurai, H. Ed.; Ellis Horwood: Chichester, 1985; Part 1, pp 25-30. (m) Brook, A. G.; Baines, K. M. Adv. Organomet. Chem. 1986, 25, pp 1-44.
(2) (a) Ando, W.; Hagiwara, T.; Migita, T. J. Am. Chem. Soc. 1973, 95, 7518. (b) Ando, W.; Sekiguchi, A.; Ogiwara, J.; Migita, T. J. Chem. Soc., Chem. Commun. 1975, 145. (c) Kreeger, R. L.; Shechter, H. Tetrahedron Lett. 1975, 2061. (d) Ando, W.; Sekiguchi, A.; Migita, T.; Kammula, S.; Green, M.; Jones, M., Jr. J. Am. Chem. Soc. 1975, 97, 3818. (e) Chapman, O. L.; Chang, C.-C.; Jung, J.; Kolc, M. E.; Lowe, J. A.; Barton, T. J.; Tumey, M. L. J. Am. Chem. Soc. 1976, 98, 7844. (f) Chedekel, M. R.; Skoglund, M.; Kreeger, R. L.; Shechter, H. J. Chem. Soc. 1976, 98, 7846. (g) Ando, W.; Sekiguchi, A.; Rothschild, A. J.; Gallucci, R. R.; Jones, M., Jr.; Barton, T. J.; Kilgour, J. A. J. Am. Chem. Soc. 1977, 99, 6995. (h) Sekiguchi, A.; Ando, W. Tetrahedron Lett. 1979, 4077. (i) Ando, W.; Sekiguchi, A.; Hagiwara, T.; Migita, T.; Chowdhry, V.; Westheimer, F. H.; Kammula, S.S.R 1980, 251, 1166. (l) Barton, T. J.; Hoekman, S. K. J. M. Chem. Soc. 1980, 102, 1584. (m) Sekiguchi, A.; Ando, W. J. Am. Chem. Soc. 1978. Am. Chem. Soc. 1981, 103, 3579. (n) Ando, W.; Tanikawa, H.; Sekiguchi, A. Tetrahedron Lett. 1983, 24, 4245. (p) Sekiguchi, A.; Ando, W. J. Am. Chem. Soc. 1981, 103, 5573. (o) Ando, W.; Tanikawa, H.; Sekiguchi, A. Tetrahedron Lett. 1984, 106, 1486. (q) Sekiguchi, A.; Ando, W. J. Am. Chem. Soc. 1981, 103, 5573. (o) Ando, W.; Tanikawa, H.; Ando, W. J. Am. Chem. Soc. 1981, 103, 5573. (o) Ando, W.; Tanikawa, H.; Ando, W. J. Am. Chem. Soc. 1984, 106, 4866. (q) Sekiguchi, A.; Ando, W. J. Am. Chem. Soc. 1981, 103, 5573. (o) Ando, W.; Tanikawa, H.; Ando, W. J. Am. Chem. Soc. 1981, 103, 5573. (o) Ando, W.; Tanikawa, H.; Ando, W. J. Am. Chem. Soc. 1981, 103, 5573. (o) Ando, W.; Tanikawa, H.; Ando, W. J. Am. Chem. Soc. 1984, 106, 1486. (q) Sekiguchi, A.; Tanikawa, H.; Ando, W. J. Am. Chem. Soc. 1984, 106, 1486. (q) Sekiguchi, A.; Tanikawa, H.;

(3) Ando, W.; Sekiguchi, A.; Migita, T. Chem. Lett. 1976, 779.

(4) Sakurai, H. J. Örganomet. Chem. 1980, 200, 261.

[†]Present address: Organosilicon Research Laboratory, Faculty of Science, Tohoku University, Sendai 980, Japan.

⁽¹⁾ For general review of silenes see: (a) Gusel'nikov, L. E.; Nametkin, N. S.; Vdovin, V. M. Acc. Chem. Res. 1975, 8, 18. (b) Ishikawa, M. Pure Appl. Chem. 1978, 50, 11. (c) Gusel'nikov, L. E.; Nametkin, N. S. Chem. Rev. 1979, 79, 529. (d) West, R.; Barton, T. J. J. Chem. Educ. 1980, 57, 334. (e) Barton, T. J. Pure Appl. Chem. 1980, 52, 615. (f) Ishikawa, M.; Kumada, M. Adv. Organomet. Chem. 1981, 19, 51. (g) Coleman, B.; Jones, M., Jr. Rev. Chem. Intermed. 1981, 4, 297. (h) Schaefer, H. F., III Acc. Chem. Res. 1982, 15, 283. (i) Armitage, D. A. In Comprehensive Organometallic Chemistry; Wilkinson, G., Ed.; Pergamon: Oxford, 1982, pp 80-86. (j) Wiberg, N. J. Organomet. Chem. 1984, 273, 141. (k) Raabe, G.; Michl, J. Chem. Rev. 1985, 85, 419. (l) Brook, A. G. In Organosilicon and Bioorganosilicon Chemistry; Sakurai, H., Ed.; Ellis Horwood: Chichester, 1985; part 1, pp 15-24. Wiberg, N. In Organosilicon and Bioorganosilicon Chemistry; Sakurai, H. Ed.; Ellis Horwood: Chichester, 1985; Part 1, pp 25-30. (m) Brook, A. G.; Baines, K. M. Adv. Organomet. Chem. 1986, 25, pp 1-44.

⁽⁵⁾ Walsh, R. Acc. Chem. Res. 1981, 14, 246.





I). It is interesting to note that the exclusive migration of a trimethylsilyl group to a carbene center was observed in both thermal and photochemical decompositions of 1. No detectable amount of methyl migration product was observed. This probably is due to the difference of the conformation of the pentamethyldisilanylcarbene. Since the Si-Si σ -bond can interact with vacant p orbitals via $\sigma-\pi$ conjugation, the conformation 9 will be more favorable than 10.



Similar selective migration of a trimethylsilyl group to a carbene center was observed in the reactions of (pentamethyldisilanyl)(trimethylsilyl)diazomethane (2). When 2 was pyrolyzed with *tert*-butyl alcohol at 450 °C under flowing nitrogen, *tert*-butoxysilane 12 arising from the silene 11 was obtained in 59% yield as sole product.⁷ Silyl enol ether 13 and vinylsilane 14 were formed in 52% and 48% yields, respectively, when 2 was pyrolyzed with acetone or benzaldehyde. Photolysis of 2 in *tert*-butyl alcohol and acetone also led to the same products, 12 and 13, in 58% and 29% yields, respectively. No methyl migration product could be found in the photo and thermal decompositions of 2 (Scheme II).

Photolysis of (tris(trimethylsilyl)silyl)(trimethylsilyl)diazomethane (3) in alcohols also cleanly produced the



Figure 1. UV spectrum in 3-MP at 77 K: (A) prior to photolysis of 1 (—); (B) after photolysis with $\lambda > 300$ nm (40 s, 80 s, 120 s, 77 K, starting material subtracted) (---); (C) after annealing and recooling to 77 K, starting material subtracted (---).



corresponding alkoxysilanes 15a and 15b in 50% and 60% yields, respectively. Silyl enol ether 16 was also obtained by the photolysis of 3 in acetone in 38% yield. Again, a methyl migration product was not found (Scheme III).

The alkoxysilane 15 was not stable under the pyrolytic conditions and underwent α -elimination to give silylene 17 and methoxytrimethylsilane. Thus, when a benzene solution of 15a was pyrolyzed at 450 °C under flowing nitrogen, 1,3-disilacyclobutane 18 and methoxytrimethylsilane were obtained as volatile products in 57% and 79% yields, respectively. The disilacyclobutane 18 is apparently formed by intramolecular insertion of silylene 17 into γ -C-H bonds on the methyl groups on silicon (Scheme IV).

Ultraviolet Spectra of Silenes. The matrix-isolation technique has been used widely for the observation of the reactive species.⁸ Although there are many reports concerning silenes, very little is known about their ultraviolet spectra.¹ The UV absorptions of silenes reported so far are (1) simple silenes such as $H_2Si=CH_2$ (258 nm), $D_2Si=CH_2$ (259 nm), and $Cl_2Si=CH_2$ (246 nm),⁹ (2) conjugated silene like silaacrylate Me₂Si=C(SiMe₃)CO₂Et (288 nm),¹⁰ (3) silaaromatics like silabenzene (212, 272, 320 nm)¹¹ and silatoluene (307, 314, 322 nm),¹² and highly

⁽⁶⁾ For the preliminary reports of polysilylated carbenes see: (a) Sekiguchi, A.; Ando, W. Chem. Lett. 1983, 871. (b) Sekiguchi, A.; Ando, W. Tetrahedron Lett. 1983, 24, 2791. (c) Sekiguchi, A.; Ando, W. Chem. Lett. 1985, 2025.

⁽⁷⁾ The silene 11 was independently generated by the salt elimination method. (a) Wiberg, N.; Preiner, G.; Schieda, O. Chem. Ber. 1981, 114, 3518. (b) Wiberg, N.; Köpf, H. J. Organomet. Chem. 1986, 315, 9.

^{(8) (}a) Chapman, O. L. Pure Appl. Chem. 1974, 40, 511. (b) Dunkin, I. R. Chem. Soc. Rev. 1980, 9, 1.

⁽⁹⁾ Maier, G.; Mihm, G.; Reisenauer, H. P. Angew. Chem., Int. Ed. Engl. 1981, 20, 597.

⁽¹⁰⁾ Sekiguchi, A.; Ando, W.; Honda, K. Tetrahedron Lett. 1985, 26, 2337.



Figure 2. UV spectrum in 3-MP at 77 K: (A) prior to photolysis of 2 (—); (B) after photolysis with $\lambda > 300$ nm (80 s, 140 s, 220 s, 77 K, starting material subtracted) (---); (C) after annealing and recooling to 77 K, starting material subtracted (---).

Table I. UV Absorptions of Silenes in 3-MP at 77 K

silene	λ_{max} , nm	precursor
Me ₂ Si=CHMe	255	Me ₃ SiCHN ₂
$Me_2Si = CHSiMe_3$ (4)	265	$Me_3SiSiMe_2CHN_2$ (1)
$Me_2Si = C(Me)SiMe_3$	274	$(Me_3Si)_2CN_2$
$Me_2Si=C(SiMe_3)_2$ (11)	278	$Me_3SiSiMe_2C(N_2)SiMe_3$ (2)

substituted silenes (Me₃Si)₂Si=C(OSiMe₃)R (ca. 340 nm) where $R = CMe_3$, CEt_3 , and 1-adamantyl.¹³ Since the selective migration of a trimethylsilyl group to a carbene center has been found, we have taken ultraviolet spectra of the silene formed in the reactions of polysilvlated diazomethanes. A dilute solution ($\sim 10^{-3}$ to $\sim 10^{-4}$ M) of 1 in 3-methylpentane (3-MP) was placed in a quartz cell and cooled to 77 K. The resulting matrix was irradiated with the filtered light of greater than 300 nm. A band with a maximum at 265 nm appeared on irradiation time (Figure The same absorption band was observed in 3-MP 1). containing tert-butyl alcohol at 77 K and immediately disappeared on annealing the matrix with concurrent formation of the trapping product 5 of the silene 4. It is quite reasonable to assume that the absorption band at 265 nm is assigned to the π - π * transition of silene 4. Similarly, silene 11 was also spectroscopically observable. Photolysis of 2 in 3-MP matrix at 77 K resulted in the formation of a band with a maximum at 278 nm (Figure 2). For comparison, UV spectra of silenes $Me_2Si = CHMe^{2e,f}$ and $Me_2Si = C(Me)SiMe_3^{2l}$ were also measured by the photolyses of (trimethylsilyl)diazomethane and bis(trimethylsilyl)diazomethane in 3-MP at 77 K, respectively. The results are summarized in Table I.¹⁴ The UV absorptions of tri- or tetrasubstituted silenes are shifted

to longer wavelength compared to the parent silene $(H_2Si=CH_2, 258 \text{ nm})$ but are at shorter wavelength than those of the highly substituted silenes (Brook's silenes, ca. 340 nm).¹³ The introduction of a trimethylsilyl group on carbon also results in a slight bathchromic shift.

In summary, the effective migratory aptitude of a trimethylsilyl group to a carbene center was observed in the reactions of polysilylated diazomethanes. This may reflect a vertical charge stabilization by the donating effect of the Si-Si σ -electrons to the vacant p orbitals of the silylcarbenes.

Experimental Section

General Data. The NMR and IR spectra were recorded on Varian EM 360A and Hitachi 260-50 spectrometers. Mass spectra were obtained on a Hitachi RMU-6M mass spectrometer and JEOL JMS-D300 spectrometer. UV spectra were recorded on a Shimazu UV-365 spectrometer. Preparative gas chromatographic separations were carried out on an Ohkura gas chromattograph with 8 mm \times 1 m, 8 mm \times 1.5 m, and 8 mm \times 2 m glass columns of 20% SF-96 on Celite 545.

Preparation of (Trimethylsilyl)diazomethane and (Pentamethyldisilanyl)diazomethane (1). (Trimethylsilyl)diazomethane (Me₃SiCHN₂) was prepared by the method of Shioiri by using ((trimethylsilyl)methyl)magnesium chloride and diphenylphosphoryl azide, (PhO)₂P(O)N₃.¹⁵ (Pentamethyldisilanyl)diazomethane (1) was also prepared by a similar manner. Thus, ((pentamethyldisilanyl)methyl)magnesium chloride was prepared by adding a solution of (chloromethyl)pentamethyldisilane (22.7 g, 0.126 mol) in ether (80 mL) to magnesium (3.68 g, 0.151 mol) with stirring under argon. To a solution of diphenylphosphoryl azide (31.1 g, 0.113 mol) in ether (100 mL) was added the Grignard reagent at ca. -20 °C. The mixture was stirred at 0 °C for 1 h and at room temperature overnight. The reaction mixture was poured into ice water and extracted with ether. The ethereal solution was dried over anhydrous sodium sulfate and concentrated. The residual yellow oil was distilled to give 1 (10.8 g, 50%): bp 62-65 °C (22 mmHg) (yellow oil); NMR (CCl₄, δ) 0.12 (s, 9 H, SiMe₃), 0.18 (s, 6 H, SiMe₂), 2.53 (s, 1 H, SiCHN₂); IR (NaCl) 2050 cm⁻¹ (C=N₂); MS, m/e 144 (M⁺ – N₂).

Preparation of (Pentamethyldisilanyl)(trimethylsilyl)diazomethane (2), (Tris(trimethylsilyl)silyl)(trimethylsilyl)diazomethane (3), and Bis(trimethylsilyl)diazomethane. Lithio(trimethylsilyl)diazomethane $[LiC(N_2)SiMe_3]$ was prepared by adding lithium diisopropylamide (LDA) (9.63 mmol) in ether (10 mL) to a solution of Me₃SiCHN₂ (1.69 g, 14.8 mmol) in ether (15 mL) at -40 °C under argon. To a solution of the $LiC(N_2)SiMe_3$ was added a solution of chloropenta-methyldisilane (1.30 g, 7.78 mmol) in ether (10 mL) at -55 °C. The mixture was stirred at 0 °C for 1 h and at room temperature for 2 h. The reaction mixture was poured into ice water and extracted with ether. The ethereal solution was dried over anhydrous sodium sulfate and concentrated. The residual yellow oil was distilled to give 2 (870 mg, 93%): bp 43-45 °C (0.4 mmHg) (yellow oil); NMR (CCl₄, δ) 0.05 (s, 9 H, SiMe₃), 0.09 (s, 9 H, SiMe₃), 0.12 (s, 6 H, SiMe₂); IR (NaCl) 2025 cm⁻¹ (C=N₂); MS, m/e 216 (M⁺ - N₂); high-resolution mass calcd for C₉H₂₄N₂Si₃ 244.1245, found 244.1244. In a similar manner, (tris(trimethylsilyl)silyl)(trimethylsilyl)diazomethane (3) was prepared in quantitative yield by the reaction of tris(trimethylsilyl)chlorosilane (2.19 g, 7.74 mmol) and LiC(N₂)SiMe₃ prepared from Me₃SiCHN₂ (1.09 g, 9.60 mmol) and LDA (9.60 mmol) in ether. After the workup, the mixture was chromatographed on a alumina column containing 10% water at 0 °C with hexane. Evaporation of the solvent afforded the yellow wax of 3: NMR (CCl_4 , δ) 0.17 (s, 9 H, SiMe₃), 0.22 (s, 27 H, SiMe₃); IR (NaCl) 2020 cm⁻¹ (C=N₂); MS m/e 360 (M⁺); high-resolution mass calcd for C₁₃H₃₆N₂Si₅ (360.1723, found 360.1716. Bis(trimethylsilyl)diazomethane was prepared by the reaction of lithio(trimethylsilyl)diazomethane with trimethylchlorosilane in ether.¹⁶

⁽¹¹⁾ Maier, G.; Mihm, G.; Reisenauer, H. P. Angew. Chem., Int. Ed. Engl. 1980, 19, 52.

⁽¹²⁾ Kreil, C. L.; Chapman, O. L.; Barton, T. J.; Burns, G. T. J. Am. Chem. Soc. 1980, 102, 841.

^{(13) (}a) Brook, A. G.; Harris, J. W.; Lennon, J.; Sheikh, M. El. J. Am. Chem. Soc. **1979**, 101, 83. (b) Brook, A. G.; Nyburg, S. C.; Abdesaken, F.; Gutekunst, B.; Gutekunst, G.; Kallury, R. K. M. R.; Poon, Y. C.; Chang, Y. -M.; Wong-Ng, W. J. Am. Chem. Soc. **1982**, 104, 5667.

⁽¹⁴⁾ Extinction coefficients cannot be given for the methodological reasons. However, the absorption bands in Table I would be $\pi - \pi^*$ transitions because the reactions were carried out with low concentrations (~10⁻³ to ~10⁻⁴ M).

⁽¹⁵⁾ Mori, S.; Sakai, I.; Aoyama, T.; Shioiri, T. Chem. Pharm. Bull. 1982, 30, 3380.

⁽¹⁶⁾ Seyferth, D.; Flood, T. C. J. Organomet. Chem. 1971, 29, C25.

Photolysis of 1 in tert-Butyl Alcohol and Acetone. A solution of 1 (85 mg, 0.49 mmol) and tert-butyl alcohol (1.5 mL) was irradiated with a high-pressure mercury lamp for 1.3 h. Separation of the reaction mixture by preparative GLC gave tert-butoxysilane 5 in 41% yield: NMR (CCl₄, δ) -0.25 (s, 2 H, SiCH₂Si), 0.00 (s, 9 H, SiMe₃), 0.10 (s, 6 H, SiMe₂), 1.23 (s, 9 H, t-Bu); IR (NaCl) 1050 cm⁻¹ (Si-O-C); MS, m/e 203 (M⁺ – Me). Anal. Calcd for C₁₀H₂₆OSi₂: C, 54.97; H, 11.99. Found: C, 55.10; H, 10.21.

Photolysis of 1 in acetone gave the silyl enol ether 6 in 28% yield: NMR (CCl₄, δ) -0.10 (s, 2 H, SiCH₂Si), 0.04 (s, 9 H, SiMe₃), 0.18 (s, 6 H, SiMe₂), 1.72 (s, 3 H, C=CMe), 3.92 (br s, 2 H, C=CH₂); IR (NaCl) 1630 (C=C) and 1050 cm⁻¹ (Si-O-C); MS, m/e 187 (M⁺ - Me). Anal. Calcd for C₉H₂₂OSi₂: C, 53.99; H, 10.95. Found: C, 53.08; H, 11.12.

Vacuum Pyrolysis of 1. The vacuum pyrolysis apparatus consisted of a Pyrex tube $(1 \times 37 \text{ cm})$ heated at 450 °C by an electric oven. The sample (93 mg, 0.54 mmol) was introduced through a septum by using a syringe at 10 mmHg. The products were collected in a trap cooled by liquid nitrogen. Separation of the reaction mixture by preparative GLC gave disilacyclobutane 7 (a mixture of trans and cis) in 53% yield: NMR (CCl₄, δ) –0.43 (s, Si₃CH), –0.40 (s, Si₃CH), –0.10 (s, SiMe₂), –0.09 (s, SiMe₃), 0.15 (s, SiMe₂), 0.20 (s, SiMe₂), 0.23 (s, SiMe₂); MS, m/e 288 (M⁺). Anal. Calcd for C₁₂H₃₂Si₄: C, 49.91; H, 11.17. Found: C, 50.02; H, 11.44.

General Pyrolysis Procedures under Flowing Nitrogen. The pyrolysis apparatus consisted of a $28 \text{ cm} \times 1 \text{ cm}$ Pyrex glass tube packed with Pyrex chips. The upper end of the tube was equipped with a rubber cap for syringe introduction of the sample and a nitrogen gas inlet. The pyrolysis tube was maintained at 450 °C, and the nitrogen flow was ca. 11 mL/min. The sample was introduced drop by drop by using a 1-mL syringe. The pyrolysates were trapped in a receiver cooled by liquid nitrogen.

Pyrolysis of 1 with tert-Butyl Alcohol, Acetone, and Benzophenone. Pyrolyses were carried out at 450 °C under flowing nitrogen. Pyrolysis of 1 (86 mg, 0.50 mmol) with tert-butyl alcohol (1.5 mL) produced the tert-butoxysilane 5 in 52% yield. Similarly, pyrolyses of 1 with acetone or benzophenone gave the silyl enol ether 6 (54%) and the vinylsilane 8 (58%),¹⁷ respectively.

Pyrolysis of 2 with tert-Butyl Alcohol, Acetone, and Benzaldehyde. Pyrolyses were carried out at 450 °C under flowing nitrogen. Pyrolysis of 2 (86 mg, 0.35 mmol) with tert-butyl alcohol (1.5 mL) produced the tert-butoxysilane 12^{7b} in 59% yield: NMR (CCl₄, δ) -0.80 (s, 1 H, Si₃CH), 0.07 (s, 18 H, SiMe₃), 0.16 (s, 6 H, SiMe₂), 1.22 (s, 9 H, t-Bu); IR (NaCl) 1040, and 1010 cm⁻¹ (Si-O-C); MS, m/e 275 (M⁺ – Me). Anal. Calcd for C₁₃H₃₄OSi₃: C, 53.71; H, 11.79. Found: C, 53.64; H, 12.01.

Pyrolysis of 2 (88 mg, 0.36 mmol) with acetone (1.5 mL) gave the silyl enol ether 13 in 52% yield: NMR (CCl₄, δ) -0.63 (s, 1 H, Si₃CH), -0.03 (s, 18 H, SiMe₃), 0.13 (s, 6 H, SiMe₂), 1.63 (s, 3 H, C=CMe), 3.77-3.92 (m, 2 H, C=CH₂); IR (NaCl) 1630 (C=C), 1040 and 1010 cm⁻¹ (Si-O-C); MS, *m/e* 375 (M⁺ - Me). Anal. Calcd for C₁₂H₃₀OSi₃: C, 52.48; H, 11.01. Found: C, 52.19; H, 11.16.

Pyrolysis of 2 (87 mg, 0.35 mmol) with benzaldehyde (1.5 mL) gave the vinylsilane 14 in 48% yield: NMR (CCl₄, δ) -0.07 (s, 9 H, SiMe₃), 0.19 (s, 9 H, SiMe₃), 7.27 (br s, 5 H, ArH), 7.83 (s, 1 H, C=CH); IR (NaCl) 1540 cm⁻¹ (C=C); MS, m/e 248 (M⁺). Anal. Calcd for C₁₄H₂₄Si₂: C, 67.66; H, 9.73. Found: C, 67.40; H, 9.80.

Photolysis of 2 in tert-Butyl Alcohol and Acetone. A solution of 2 (86 mg, 0.35 mmol), tert-butyl alcohol (1.5 mL), and benzene (0.5 mL) was irradiated with a high-pressure mercury lamp for 2 h. tert-Butoxysilane 12 was obtained in 58% yield. Similarly, photolysis of 2 in acetone gave the silyl enol ether 13 in 29% yield.

Photolysis of 3 in Methanol, tert-Butyl Alcohol, and Acetone. A solution of 3 (89 mg, 0.25 mmol), tert-butyl alcohol (1.5 mL), and benzene (0.5 mL) was irradiated with a high-pressure mercury lamp for 1.4 h. Separation of the reaction mixture by preparative GLC gave the *tert*-butoxysilane **15b** in 60% yield: NMR (CCl₄, δ) -0.53 (s, 1 H, Si₃CH), 0.06 (s, 18 H, SiMe₃), 0.12 (s, 18 H, SiMe₃), 1.18 (s, 9 H, *t*-Bu); IR (KBr) 1030 and 1015 cm⁻¹ (Si-O-C). Anal. Calcd for C₁₇H₄₆OSi₅: C, 50.17; H, 11.39. Found: C, 49.93; H, 11.57.

Photolysis of 3 (1671 mg, 4.59 mmol) in methanol for 4.3 h produced the methoxysilane 15a in 50% yield: mp 140–142 °C; NMR (CCl₄, δ) –0.02 (s, 18 H, SiMe₃), 0.10 (s, 18 H, SiMe₃), 3.33 (s, 3 H, OMe), and the signal of the methine proton on carbon coincides with those of trimethylsilyl group; ¹³C NMR (CDCl₃, δ) 0.94 (q, SiMe₃), 3.60 (q, SiMe₃), 6.25 (d, Si₃CH), 53.27 (q, OMe); IR (KBr) 1100 and 1010 cm⁻¹ (Si–O–C); MS, m/e 349 (M⁺ – Me). Anal. Calcd for C₁₄H₄₀OSi₅: C, 46.08; H, 11.04. Found: C, 46.02; H, 11.23.

Photolysis of 3 (89 mg, 0.25 mmol) in acetone gave the silyl enol ether 16 in 38% yield: NMR (CCl₄, δ) -0.02 (s, 18 H, SiMe₃), 0.07 (s, 18 H, SiMe₃), 0.19 (s, 1 H, Si₃CH), 1.58 (s, 3 H, C=CMe), 3.70 (br s, 1 H, C=CH), 3.85 (br s, 1 H, C=CH); IR (KBr) 1640 (C=C), 1030 cm⁻¹ (Si-O-C); MS, m/e 375 (M⁺ – Me). Anal. Calcd for C₁₆H₄₂OSi₅: C, 49.16; H, 10.83. Found: C, 49.03; H, 10.62.

Pyrolysis of Methoxysilane 15a. A solution of methoxysilane 15a (108 mg, 0.30 mmol) and benzene (1.5 Ml) was pyrolyzed at 450 °C under flowing nitrogen. Separation of the reaction mixture by preparative GLC gave methoxytrimethylsilane (79%) and disilacyclobutane 18 (57%). Compound 18: NMR (CCl₄, δ) -0.33 $(d, J = 7 Hz, 1 H, Si_3CH), -0.08 (s, 9 H, SiMe_3), 0.09 (s, 9 H,$ $SiMe_3$, 0.18 (s, 3 H, SiMe), 0.24 (s, 3 H, SiMe), 4.35 (q, J = 7Hz, 1 H, SiH), the signals of the ring methylene protons are superimposed on those of two trimethylsilyl group, but the integration of the silvl region signals shows these should arise from 27 protons in total; $^{13}\breve{C}$ NMR (CDCl_3, $\delta)$ –4.42 (SiCH_2Si), –1.93 (SiMe₃), 1.21 (SiMe₃), 1.76 (Si₃CH), 2.51 (SiMe), 4.57 (SiMe), SiCH₂Si and Si₃CH carbons were easily differentiated for SiMe carbons by INEPT technique; IR (NaCl) 2070 cm⁻¹ (SiH); MS, m/e 260 (M⁺). Anal. Calcd for C₁₀H₂₈Si₄: C, 46.07; H, 10.82. Found: C, 46.05; H, 11.02.

Photolysis of Silyldiazomethanes 1 and 2, (Trimethylsilyl)diazomethane, and Bis(trimethylsilyl)diazomethane in 3-MP Matrix at 77 K. A mixture of 1 (ca. 0.1 mg) and 3-methylpentane (3-MP) (5 mL) was placed in a quartz UV cell and degassed for several times. The mixture was cooled to 77 K, and the resulting matrix was irradiated through a filter ($\lambda >$ 300 nm). The ultraviolet absorptions were taken at periodic intervals. An absorption band with a maximum at 265 nm appeared and grew on irradiation (Figure 1). The same absorption band was observed in 3-MP containing tert-butyl alcohol at 77 K and immediately disappeared on annealing the matrix. Gcmass spectrometry revealed the formation of tert-butoxysilane 5. Similarly, silyldiazomethane 2, (trimethylsilyl)diazomethane, and bis(trimethylsilyl)diazomethane was irradiated in 3-MP at 77 K with $\lambda > 300$ nm, giving absorption bands at 278, 255, and 274 nm, respectively, due to the corresponding silenes. These bands immediately disappeared on annealing the matrix.

Acknowledgment. We are grateful to the Shin-etsu Chemical Co. for a gift of chlorosilanes. This research is supported by Grant-in-Aid for Scientific Research (No. 61740280).

Registry No. 1, 87161-27-1; 2, 87161-28-2; 3, 86997-48-0; 4, 18143-89-0; 5, 87161-29-3; 6, 87161-30-6; trans-7, 82113-62-0; cis-7, 82113-61-9; 8, 51318-07-1; 9, 87161-33-9; 11, 62139-73-5; 12, 87161-31-7; 13, 80431-41-0; 14, 18415-23-1; 15a, 86997-46-8; 15b, 87161-32-8; 16, 87161-34-0; 18, 86997-49-1; LiC(N₂)SiMe₃, 84655-21-0; (Me₃Si)₃SiCl, 5565-32-2; Me₂Si=CHMe, 55395-25-0; Me₃SiCHN₂, 18107-18-1; (Me₃Si)₂CN₂, 30006-66-7; Me₃SiS-(Me₂)CH₂Cl, 5181-46-4; (Pho)₂P(O)N₃, 26386-88-9; Me₃SiSiMe₂Cl, 1560-28-7; Me₃SiCl, 75-77-4; t-BuOH, 75-65-0; Me₃SiOMe, 1825-61-2; 3-MP, 96-14-0; benzaldehyde, 100-52-7.

⁽¹⁷⁾ Gröbel, B. -T.; Seebach, D. Chem. Ber. 1977, 110, 852.